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## Enhanced thermoelectric properties of $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$ hybrid thin films by post-annealing

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In this work, to improve the  $ZT$  value of  $\text{Sb}_2\text{Te}_3$ , a novel concept of inorganic-organic hybridization is presented and the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films have been prepared via a post-annealing involved sequential sputtering/evaporating method. Results show that the crystallinity of the thin films are greatly improved after post-annealing and also with preferential orientations of (006) and (009) at appropriate temperature, leading to an obvious enhancement of electrical conductivity. Additionally, the hybrid thin films show uniform nano-sized grainy structures and the organic  $\text{CH}_3\text{NH}_3\text{I}$  has been successfully incorporated into the hybrid system in a stable state, thus resulting in the increase of Seebeck coefficient and decrease of thermal conductivity based on energy filtering effect. As expected, a maximum room-temperature  $ZT$  value of 0.56 for the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin film annealed at 573 K can be obtained. This outcome further demonstrates a great potential for the inorganic-organic hybrid thin film in low temperature application scenarios.

### Introduction

Thermoelectric (TE) materials can directly convert heat energy to electricity and have great potential applications in semiconductor cooling and power generator fields.<sup>[1]</sup> The development of TE generators for small electronic devices as the self-powered components has drawn tremendous research attentions due to its continuous power supply by using heat from other devices.<sup>[2]</sup> However, conventional TE materials are relatively bulky and naturally brittle, thereby limiting the development of micro-TE devices. By contrast, thin film TE materials are lightweight and easily prepared on various types of substrates, offering the possibility for micro-sized TE devices with broad applications in bendable and miniature scenarios.<sup>[3-6]</sup> The efficiency of the TE generator is determined by the properties of its intrinsic materials, which is closely related to a dimensionless figure of merit, expressed as  $ZT = S\sigma T / \kappa$ , where  $S$

is the Seebeck coefficient,  $\sigma$  is the electrical conductivity,  $T$  is the absolute temperature and  $\kappa$  is thermal conductivity.<sup>[7]</sup> Thus, simultaneously modifying  $S$ ,  $\sigma$ , and  $\kappa$  to obtain TE material with high  $ZT$  value is essential to realize the efficient conversion for widespread commercial TE device applications. Recently, a new concept of TE performance improvement involved with inorganic-organic thin film TE nanocomposite materials has emerged. To be specific, combining the inorganic and organic components not only enhances the TE properties thanks to an energy filtering effect, but also extends the flexibility of inorganic materials.<sup>[8-11]</sup> For instance, Jin et al. fabricated  $\text{Bi}_2\text{Te}_3$  thin film composites with highly ordered (0001)-textured nanocrystals on high-quality single-walled carbon nanotube (SWCNT) bundles by using sputtering method, demonstrating high  $ZT$  value and superior flexibility.<sup>[8]</sup> Zhang et al. prepared a p-type  $\text{Bi}_{0.5}\text{Sb}_{1.5}\text{Te}_3/\text{PEDOT:PSS}$  hybrid thin film that has over 2000% enhancement in the power factor.<sup>[9]</sup>

Classic antimony telluride-based thin films are well known as efficient thermoelectric materials that have been intensively studied and widely applied. For the thin film deposition, various techniques such as sputtering,<sup>[11-15]</sup> evaporation,<sup>[16]</sup>

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electron-deposition<sup>[17,18]</sup> and chemical vapor deposition<sup>[19]</sup> have been applied successfully. As aforementioned, the construction of an inorganic-organic hybrid framework can greatly enhance its pristine TE properties. An important organic material of  $\text{CH}_3\text{NH}_3\text{I}$  originated from inorganic-organic perovskite solar cells<sup>[20-23]</sup> was selected as the organic component in our previous work. Indeed, crystalline  $\text{CH}_3\text{NH}_3\text{I}$ -based materials have excellent electrical transport characteristic with carrier mobility as high as  $10 \text{ cm}^2 \text{ V}^{-1} \text{ S}^{-1}$ , which is beneficial for thermoelectric materials to obtain more superior thermoelectric properties. The  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin film prepared by using the multilayer deposition method has dramatically enhanced the Seebeck coefficient as well as a decrease of thermal conductivity, resulting in a significant increase of  $ZT$  compared with pure  $\text{Sb}_2\text{Te}_3$  thin film.<sup>[24]</sup> However, the obtained TE properties are still somewhat unsatisfactory and obviously lower than those of the bulk antimony telluride-based materials. For example, Luo et al. reported a  $ZT$  value over 1.7 of  $\text{Sb}_2\text{Te}_3$  could be obtained under high magnetic field,<sup>[25]</sup> and a value of 1.5 was also achieved after  $\text{FeTe}_2$  doping as reported by Shin et al.<sup>[26]</sup> Therefore, improving its  $ZT$  value especially for the low temperature advantageous scenarios to broaden the scope of thin film based applications needs further exploration. In this work, the high-quality inorganic-organic  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films were prepared by using magnetron sputtering combined with thermal evaporation method. The effect of post-annealing temperature on the TE properties was systematically investigated. As the result, a  $ZT$  value over 0.5 at room temperature of the hybrid thin film has been successfully obtained, surpassing the pure  $\text{Sb}_2\text{Te}_3$  thin film and comparable with the maximum values of the  $\text{Sb}_2\text{Te}_3$ -based materials.

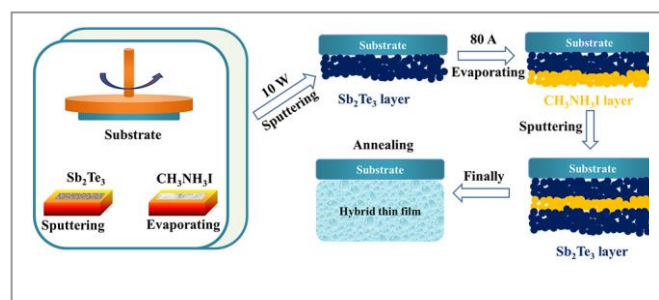
## Experimental

### Preparation of $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$ hybrid thin films

At first, methylammonium iodide ( $\text{CH}_3\text{NH}_3\text{I}$ ) and was synthesized by using methylamine ( $\text{CH}_3\text{NH}_2$ , Sigma Aldrich, 57 wt.% in  $\text{H}_2\text{O}$ ) and hydroiodic acid (HI, Sigma Aldrich, 40 wt.% in  $\text{H}_2\text{O}$ ) as raw materials. A mixture of 28 ml  $\text{CH}_3\text{NH}_2$  and 30 ml HI was loaded into a 250 ml flask and stirred at  $0^\circ\text{C}$  for 2 hours to form homogeneous precursor solution. Then it was transferred

to a beaker and kept in a fixed temperature of  $95^\circ\text{C}$  until obtaining the as-expected white  $\text{CH}_3\text{NH}_3\text{I}$  powder. The final purification process was carried out with diethyl ether for three times and the high-purity crystalline  $\text{CH}_3\text{NH}_3\text{I}$  powder can be obtained after drying at  $60^\circ\text{C}$  in a vacuum chamber for 10 hours.

The  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  inorganic-organic hybrid thin films were prepared through a post-annealing involved sequential sputtering/evaporating method. A schematic illustration of the preparation process is shown in Fig. 1. Prior to deposition, the 1.5 mm BK7 glass was sequentially cleaned with acetone, alcohol, and deionized water for 15 min, and then dried under  $\text{N}_2$  gas. The vacuum chamber was evacuated to an ultrahigh vacuum ( $2.0 \times 10^{-4} \text{ Pa}$ ) prior to deposition. Initially, a high-purity  $\text{Sb}_2\text{Te}_3$  (99.99%) sputtering target purchased from HZAM Co., Ltd was used, the  $\text{Sb}_2\text{Te}_3$  layer was deposited onto the glass substrate with a thickness of approximately 200 nm by magnetron sputtering with a fixed power of 10 W. Then the  $\text{CH}_3\text{NH}_3\text{I}$  layer was evaporated onto the  $\text{Sb}_2\text{Te}_3$  layer at a current of 100 A to a thickness of 100 nm. This evaporation process was carried out by a vacuum evaporating apparatus equipped in the same chamber and using the as-prepared  $\text{CH}_3\text{NH}_3\text{I}$  powder as source. Thereafter, another  $\text{Sb}_2\text{Te}_3$  precursor layer was deposited onto the  $\text{CH}_3\text{NH}_3\text{I}$  layer to form a sandwich-structured inorganic-organic composite thin film. Finally, the thin films were post-annealed for 1 h under an Ar atmosphere with variable annealing temperatures.



**Fig. 1** Schematic illustration of the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films preparation process.

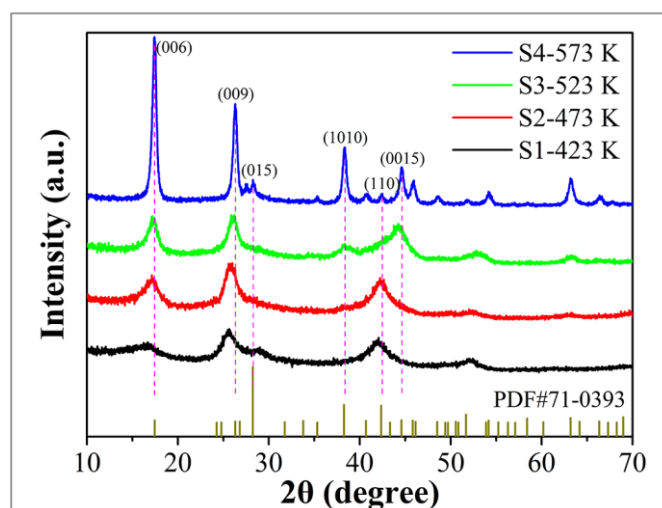
### Characterization

The crystal structure of the thin films was investigated through X-ray diffraction (XRD, D/max2500, Rigaku Corporation) with  $\text{Cu}/\text{K}\alpha$  radiation at a voltage of 40 kV and a counting duration

of  $10^\circ/\text{min}$  ranging from  $10^\circ$  to  $70^\circ$ . Morphologies and elemental composition of the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films were obtained from a Zeiss supra 55 thermal field emission scanning electron microscope (SEM) equipped with an EDAX instrument. The room-temperature Raman scattering measurements were performed using a Lab Ram XploRA spectra system (Horiba Jobin Yvon). A steady-state spectrometer (Zolix Scan) equipped with a 325 nm HeCd laser as the excitation source was used to obtain photoluminescence (PL) spectra. The chemical valence was determined by conducting X-ray photoelectron spectroscopy (XPS, ESCALAB 250Xi) with a monochromatic Al K $\alpha$  X-ray source of 1486.6 eV. The electrical conductivity and the Seebeck coefficient were simultaneously measured at room temperature by the Potential-Seebeck-Microprobe (PSM, Quantum Design) with a considered 7% instrument error. The carrier concentration and the Hall mobility were characterized using a Hall-effect measurement system (HL5500PC, Nanometrics) with Van der Pauw configuration at room temperature. The thermal conductivity at room temperature was determined by a transient hot-wire theory method (TC3000, Xiayi Electronic Technology). To obtain the reliable value, each sample was measured for ten times and average value was used also with an estimated error of approximately 10%.

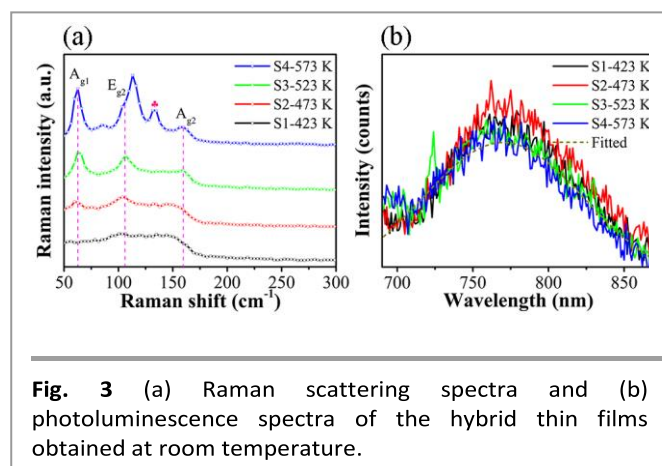
## Results and discussion

Fig. 2 shows the XRD patterns of the as-prepared  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films with different post-annealing temperatures. The diffraction peaks belonging to sample S1 annealed at 423 K present large full-width half maximum and low intensities, suggesting its poor crystallinity under this lower temperature circumstance. Then temperature-induced thin film crystallinity improvement can be observed also with a preferential orientation of (006) and (009). When the post-annealing temperature reached up to 573 K, all the sharp and prominent peaks are in agreement with the JCPDS standard card (71-0393) of the hexagonal phase of  $\text{Sb}_2\text{Te}_3$  without any detectable impurity. The absence of an observable second phase of  $\text{CH}_3\text{NH}_3\text{I}$  is probably due to its low content.



**Fig. 2** XRD patterns of the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films.

To further investigate the crystalline nature and also the interior structures of the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films, Raman analysis has been carried out using a 514.5 nm laser in the range from  $50\text{ cm}^{-1}$  to  $300\text{ cm}^{-1}$ . As shown in Fig. 3a, no obvious peaks can be observed for sample S1, indicating its poor crystallization, which is consistent with the XRD results. With increasing the post-annealing temperature, some distinct peaks start to emerge and strengthen due to the improvement of thin film crystallinity. According to the theoretical calculations and previous experimental results, three major peaks located at 63, 106, and  $159\text{ cm}^{-1}$  can match well with the  $A_{g1}$ ,  $E_{g2}$ , and  $A_{g2}$  vibration modes of the  $\text{Sb}_2\text{Te}_3$ , respectively.<sup>[27]</sup> A slightly right shift of  $E_{g2}$  for the sample S4 is closely related to the incorporation of  $\text{CH}_3\text{NH}_3\text{I}$  after a high temperature post-annealing. Moreover, an additional peak at  $133\text{ cm}^{-1}$  can be



**Fig. 3** (a) Raman scattering spectra and (b) photoluminescence spectra of the hybrid thin films obtained at room temperature.

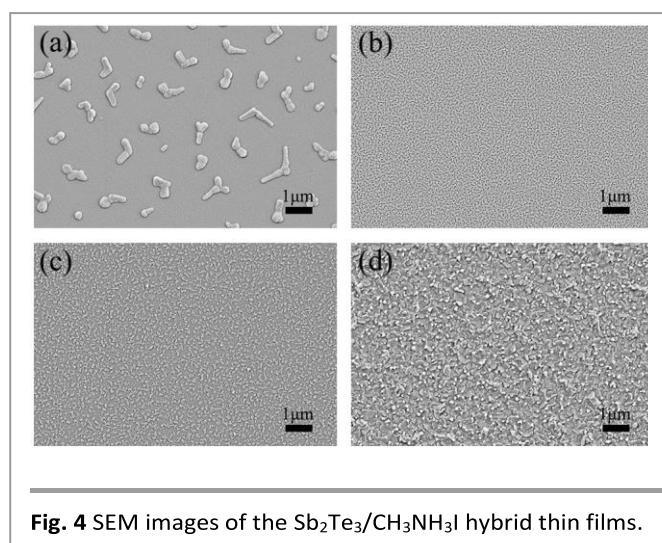


identified as the vibration mode of the  $\text{CH}_3\text{NH}_3\text{I}$  based perovskite tetragonal crystal structure,<sup>[27,28]</sup> implying the existence of this second phase. Photoluminescence spectra is also an effective tool for organic component characterization, Fig. 3b shows the corresponding results of the hybrid thin films, one observable broad peak located at  $\sim 770$  nm belonging to  $\text{CH}_3\text{NH}_3\text{I}$  further confirming that the as-prepared thin film consists of inorganic-organic hybrid structures.<sup>[29]</sup>

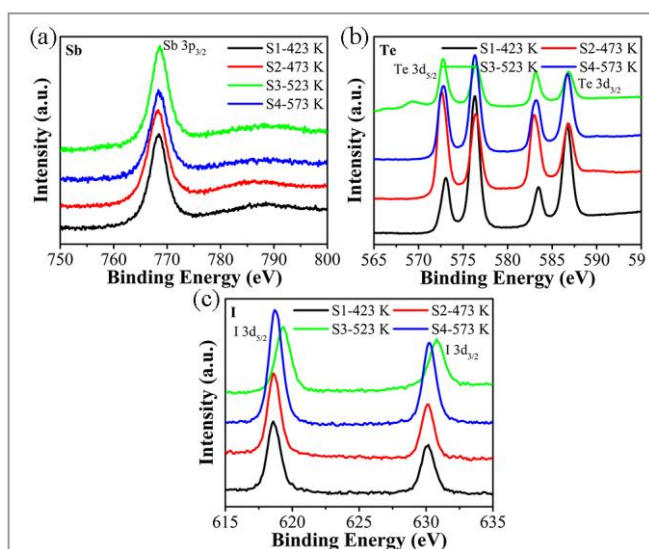
Fig. 4 presents the SEM images of the thin films, where temperature-induced surface morphology evolution has been clarified. A number of large clusters randomly dispersed on the surface can be observed for sample S1 (Fig. 4a), indicating the organic components have not been fully incorporated and exposed to a low post-annealing temperature. Significant decomposition and diffusion of these clusters occurred with an increase in the annealing temperature, leading to uniform nano-sized grainy structures in the thin film. Importantly, the as-designed sandwich-structure with  $\text{CH}_3\text{NH}_3\text{I}$  layer embedded in the middle position is really beneficial for this diffusion under post-annealing treatment. Further increasing the temperature to 573 K, as shown in Fig. 4d, sample S4 exhibits cocked plate-shaped features, implying the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin film has a preferential growth direction that is perpendicular to the substrate, which is also consistent with the XRD results with (006) and (009) preferential orientation. Moreover, the dense and shaped plates with an average size of  $\sim 200$  nm can benefit the charge transport properties and provide additional scattering centers to the propagation of

phonons, thus resulting in a reduced thermal conductivity and also an increased Seebeck coefficient. The representative I content belonging to organic component of  $\text{CH}_3\text{NH}_3\text{I}$  has also been obtained from SEM-coupled EDS analysis, a slight decrease of atomic percent from 1.90% to 1.50% with increasing the post-annealing temperature further indicating it is essential to control the temperature.

XPS analysis was further conducted to investigate the valence states of the representative three constitute elements of Sb, Te and I. The corresponding high-resolution core level spectra obtained from all the hybrid thin films are shown in Fig. 5. A sharp peak located at 768.5 eV associated with  $\text{Sb } 3p_{3/2}$  is depicted in Fig. 5a, and no obvious modification can be observed with increasing the post-annealing temperature. Additionally, a high-resolution scan of Te 3d region (Fig. 5b) shows peaks at about 572.6 eV and 583.1 eV, which effectively match the reported values for the binding energies of  $\text{Te } 3d_{5/2}$  and  $\text{Te } 3d_{3/2}$  of  $\text{Bi}_2\text{Te}_3$ , respectively.<sup>[27]</sup> The other two peaks that synchronously exist toward higher binding energies at approximately 576.3 eV and 586.7 eV indicate the existence of oxidized states ( $\text{Te}^{4+}$ ) on the surface, which is reasonable to occur after post-annealing of this composite thin film.<sup>[30]</sup> Finally, the spin orbit-coupled doublet of the I 3d core levels of all the thin films are split into  $3d_{5/2}$  ( $\sim 618.7$  eV) and  $3d_{3/2}$  ( $\sim 630.2$  eV) with a separation binding energy value of 11.5 eV,



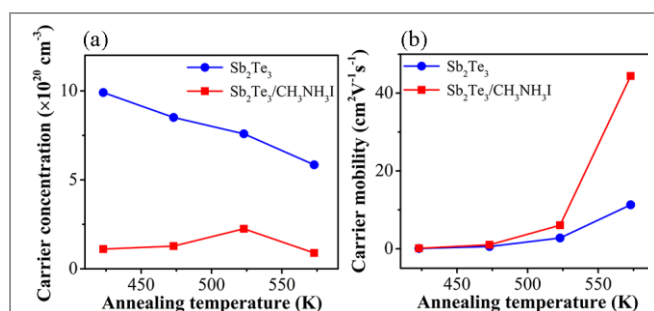
**Fig. 4** SEM images of the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films.



**Fig. 5** XPS spectra of (a) Sb 3p, (b) Te 3d and (c) I 3d for the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films.

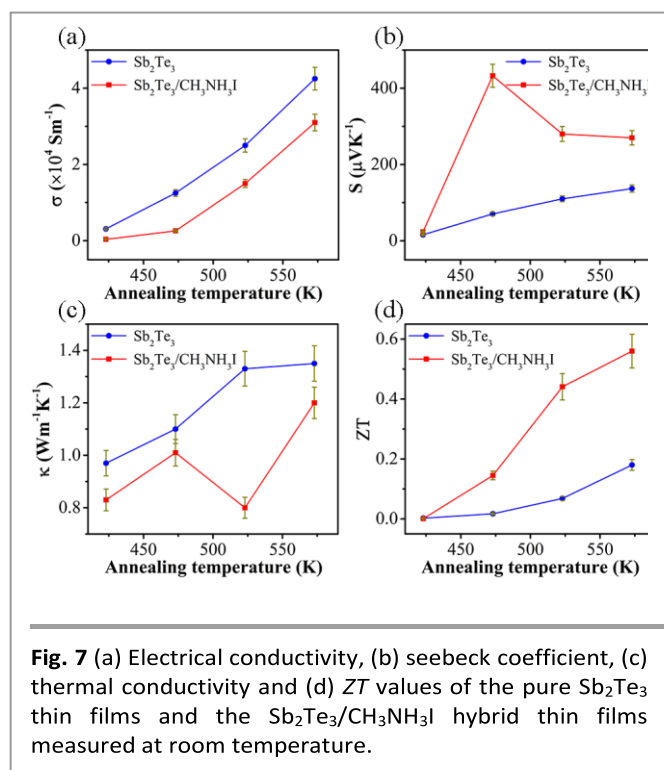
which is the typical peak position and separation of the spin-orbit components for  $\Gamma^-$ , further confirming that the organic  $\text{CH}_3\text{NH}_3\text{I}$  has been incorporated into the hybrid system in a stable state.

In the subsequent study, for a better comparison, the pure  $\text{Sb}_2\text{Te}_3$  thin films with the same annealing treatment procedures have been prepared and denoted as P1, P2, P3 and P4, respectively. The Hall carrier concentration ( $n$ ) and Hall carrier mobility ( $\mu$ ) of the pure  $\text{Sb}_2\text{Te}_3$  thin films as well as the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films have been experimentally determined at room temperature and illustrated in Fig. 6. As shown in Fig. 6a, the pure  $\text{Sb}_2\text{Te}_3$  thin film post-annealed at 423 K (sample P1) has a carrier concentration  $n$  as high as  $9.91 \times 10^{20} \text{ cm}^{-3}$ , which is comparable to that of the reported bulk materials. As the post-annealing temperature increases, a significant linear decrease of  $n$  value can be observed, and it is closely related to the reduction of defect numbers after a more complete crystallization at high temperature. The temperature-induced grain growth and structure densification also lead to reduce the scattering of free electrons and therefore increasing the carrier mobility. This phenomenon resulted in a remarkable increase of carrier mobility  $\mu$  from  $0.08 \text{ cm}^2 \text{ V}^{-1} \text{ S}^{-1}$  at 423 K to  $11.3 \text{ cm}^2 \text{ V}^{-1} \text{ S}^{-1}$  at 573 K for the pure  $\text{Sb}_2\text{Te}_3$  thin films. Importantly, for the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films, an obvious decrease of Hall carrier concentration can be attributed to an enhanced scattering effect with adding the organic components as scattering centers. Meanwhile, the intrinsic n-type characteristic of  $\text{CH}_3\text{NH}_3\text{I}$  can also cause the recombination of partial electrons and holes, thus further reducing the carrier concentration of the hybrid thin film. Temperature-induced carrier mobility increase thanks to the improved crystallinity has also been observed in the hybrid thin films. Specifically, the  $\mu$  values also show an increase of about 2-4 times compared with those of the pure  $\text{Sb}_2\text{Te}_3$  thin films, and it is closely related to the formation of denser nanostructures in the existence of organic  $\text{CH}_3\text{NH}_3\text{I}$ . The enhanced carrier mobility (up to  $44.4 \text{ cm}^2 \text{ V}^{-1} \text{ S}^{-1}$ ) yields to a longer recombination life-time for carriers, which is undoubtedly beneficial for the migration of the electron/hole.



**Fig. 6** Hall-effect measurements for the pure  $\text{Sb}_2\text{Te}_3$  thin films and the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films: (a) Hall carrier concentration and (b) Hall carrier mobility.

Fig. 7 shows the room temperature thermoelectric properties of all the pure  $\text{Sb}_2\text{Te}_3$  thin films and the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films. The corresponding values with attached error bars are determined by the measuring values with considered instrument errors and measuring errors. Fig. 7a presents the experimentally determined electrical conductivity  $\sigma$  of all the samples. A similar positive relationship between  $\sigma$  and post-annealing temperature can be observed for both pure  $\text{Sb}_2\text{Te}_3$  thin films and  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films. According to the typical expression of  $\sigma = ne\mu$ , where  $n$  is the carrier concentration,  $\mu$  is the carrier mobility and  $e$  is the unit charge.<sup>[31]</sup> Thus, the carrier mobility is the dominant factor that accounts for the increase of electrical conductivity in the presence of a decreased carrier concentration as depicted previously. Moreover, the maximum  $\sigma$  values are  $4.25 \times 10^4 \text{ S m}^{-1}$  and  $3.1 \times 10^4 \text{ S m}^{-1}$  for the  $\text{Sb}_2\text{Te}_3$  thin film and  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin film post-annealed at 573 K, respectively. This slight decrease is mainly caused by the decreased  $n$  value after incorporating the organic component, which cannot be fully compensated by the enhanced  $\mu$  value. The Seebeck coefficients  $S$  of the thin films remain positive at those four different annealing temperatures, indicating their P-type nature, even after the incorporation of organic component (Fig. 7b). A normal quasi-linear positive relationship between the  $S$  values and the post-annealing temperatures for pure  $\text{Sb}_2\text{Te}_3$  thin films can be explained by the reduction of some ionized impurities and improvement of crystallinity with increasing temperature. By contrast, the  $S$  values are obviously increased after the incorporation of  $\text{CH}_3\text{NH}_3\text{I}$  and reach a maximum value of  $432.6 \text{ } \mu\text{V K}^{-1}$  at 473 K



for the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin film. This improvement of  $S$  should be partially results from the reduced carrier concentration based on the Pisarenko relation.<sup>[32]</sup> Additionally, the band bending at the interfaces between the inorganic-organic inclusions can produce a significant scattering effect that might preferentially scatter low energy charge carriers, which can also enhance density of states and effective mass of carriers, thus are beneficial to the increase of  $S$  values.

The total thermal conductivity  $k$  measured at room temperature is shown in Fig. 7c. The  $k$  value of the pure  $\text{Sb}_2\text{Te}_3$  thin film post-annealed at 423 K (sample P1) is  $0.97 \text{ W m}^{-1} \text{ K}^{-1}$ , which is lower than that of the bulk  $\text{Sb}_2\text{Te}_3$  owing to its poor crystallinity. With increasing the post-annealing temperature, a significant increase of  $k$  value can be observed and it could inevitably diminish the improvement of final ZT value. By contrast, all the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films have a lower  $k$  value, especially an interesting value as low as  $0.8 \text{ W m}^{-1} \text{ K}^{-1}$  for the highly crystalline inorganic-organic hybrid thin film post-annealed at 523 K (sample S3). Explanatorily, after the incorporation of organic  $\text{CH}_3\text{NH}_3\text{I}$ , it can scatter more phonons thanks to the existence of organic particles and defects. Moreover, the added abundant nanoscale or mesoscale boundaries between the inorganic and organic structures will

further increase the effective scattering of phonons. Overall, this hybrid structure induced thermal conductivity decrease will undoubtedly beneficial for the improvement of ZT value. As shown in Fig. 7d, the calculated ZT values can be increased up to 8.5 times, 6.5 times and 3.1 times when comparing the hybrid thin films and the pure  $\text{Sb}_2\text{Te}_3$  thin films with annealing treatment at 473 K, 523 K and 573 K, respectively. Notably, a maximum ZT value of 0.56 at room temperature for the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin film is comparable with the maximum values of the  $\text{Sb}_2\text{Te}_3$ -based thermoelectric materials.<sup>[19,21]</sup> Furthermore, a ZT value of 0.15 for the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin film annealed at 473 K is comparable with 0.18 for the pure  $\text{Sb}_2\text{Te}_3$  thin film annealed at 573 K. This obvious 100 K net further demonstrates a great potential for the inorganic-organic hybrid thin film in low temperature application scenarios.

## Conclusions

In summary, an effective magnetron sputtering combined with thermal evaporation method has been used to prepare the inorganic-organic  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thermoelectric thin films. The post-annealing process induced crystallization, surface morphology evolution as well as the construction of a stable hybrid framework of the thin films can be observed. Moreover, with increasing the annealing temperature, the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin films exhibit an obvious improvement in electrical conductivity and Seebeck coefficient. Thanks to its effective scattering of phonons in the hybrid structure, a decrease of thermal conductivity is also beneficial for the TE performance improvement. As a result, a ZT value as high as 0.56 at room temperature for the  $\text{Sb}_2\text{Te}_3/\text{CH}_3\text{NH}_3\text{I}$  hybrid thin film has been successfully obtained, which is totally surpassing the pure  $\text{Sb}_2\text{Te}_3$  thin film and is comparable with the maximum values of the  $\text{Sb}_2\text{Te}_3$ -based thermoelectric materials, further demonstrating its great application potential in low temperature scenarios.

## Conflicts of interest

There are no conflicts to declare.

## Acknowledgements

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